



1374.39158CX1

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Hasegawa et al.
Serial No.: 10/770,413
Filed: February 4, 2004
Title: METHOD OF MANUFACTURING SEMICONDUCTOR
INTEGRATED CIRCUIT DEVICES
Group: 1756
Examiner: CHACKO DAVIS, Daborah
Confirmation No.: 1925

COMMENTS ON STATEMENT OF REASONS FOR ALLOWANCE

Mail Stop: Issue Fee

Commissioner for Patents

P.O. Box 1450

Alexandria, Virginia 22313-1450

December 13, 2006

Sir:

Applicants note that in the Reasons for Allowance at page 2 of the Notice of Allowability dated September 5, 2006, the Examiner sets forth that "claims 1-18, are allowable over the prior art of record (U.S. Patent No. 6,327,022 (Nishi), U.S. Patent No. 6,544,721 (Saito), and U.S. Patent No. 6,103,428 (Hatai et al.)) because the prior art of record does not disclose the method of forming a semiconductor device wherein the phase of the light passing through all of the hole patterns of the first layout pattern is inverted from a phase of the light passing through all the hole patterns of the second layout pattern corresponding to the hole pattern of the first layout pattern."

In citing the art of record, Applicants note that the Examiner has omitted Japanese Patent No. JP 06-83032. This reference was included in the IDS filed with the application, and initialed by the Examiner on the Office Action dated March 28,


2005. In view of this reference, Applicants believe that the Reasons for Allowance should include this reference as follows:

"Claims 1-18, are allowable over the prior art of record (JP 06-83032, U.S. Patent No. 6,327,022 (Nishi), U.S. Patent No. 6,544,721 (Saitoh), and U.S. Patent No. 6,103,428 (Natal et al.)) because the prior art of record does not disclose a method of forming a semiconductor device wherein the phase of the light passing through all of the hole patterns of the first layout pattern is inverted from a phase of the light passing through all the hole patterns of the second layout pattern the same as the first layout pattern on the same mask substrate as the first layout pattern corresponding to the hole pattern of the first layout pattern."

If the Examiner believes that there are any matters which can be resolved by way of either a personal or telephone interview, the Examiner is invited to contact Applicants' undersigned attorney at the number indicated below.

Applicants request any shortage or excess in fees in connection with the filing of this paper, including extension of time fees, and for which no other form of payment is offered, be charged or credited to Deposit Account No. 01-2135 (Case: 1374.39158CX1).

Respectfully submitted,
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LDT/vvr

Dated: December 13, 2006